

Notice of References Cited	Application/Control No. 10/679,844		Applicant(s)/Patent Under Reexamination STOKOWSKI ET AL.	
	Examiner Michael P. Stafira		Art Unit 2877	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,466,315	10-2002	Karpol et al.	356/237.4
	B	US-6,268,093	07-2001	Kenan et al.	430/30
	C	US-6,184,976	02-2001	Park et al.	356/237.4
	D	US-2003/0207475	11-2003	Nakasuji et al.	438/14
	E	US-6,691,052	02-2004	Maurer, Wilhelm	702/81
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)				
	U	Anton Barty, "Aerial Image Microscopes for the inspection of defects in EUV masks" 2002, 22 nd Annual BACUS Symposium on Photomask Technology, SPIE Vol. 4889 (2002).				
	V	Pei-yang, "Printability of Pellicle Defects in DUV 0.5 um Lithography" 1991, SPIE Vol. 1604 11 th Annual BACUS Symposium on Photomask Technology (1991).				
	W					
	X					

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.